In the Claims:

1-18. (Canceled)

19. (Previously presented) The electrical structure of claim 26, wherein the electrical structure further comprises a chromium oxide layer on the chromium volume.

20. (Previously presented) The electrical structure of claim 26, wherein the acid solution includes hydrochloric acid in a liquid bath form.

21. (Previously presented) The electrical structure of claim 26, wherein the acid solution includes hydrochloric acid in a spray form.

22. (Previously presented) The electrical structure of claim 26, wherein said iron-comprising body includes steel.

23-25. (Canceled)

26. (Previously presented) An electrical structure, comprising:

a chromium volume, wherein the chromium volume includes a layer of chromium;

an iron-comprising body;

an acid solution; and

a layer of conductive metal on the layer of chromium, wherein the conductive metal includes an opening extending through its thickness, wherein a portion of the iron-comprising body is within the opening, wherein the portion of the iron-comprising body is in electrical contact with the chromium volume, and wherein a portion of the acid solution is within the opening, and wherein the portion of the acid solution is in contact with both the portion of the iron-comprising body and the chromium volume.

27. (Previously presented) The electrical structure of claim 26, wherein the layer of conductive metal includes a metal selected from the group consisting of copper, aluminum, nickel, silver, and gold.

28. (Previously presented) The electrical structure of claim 26, wherein the iron-comprising body includes steel, and wherein the chromium volume includes the metallic chromium.

29. (Previously presented) The electrical structure of claim 26, wherein the chromium volume includes the metallic chromium, wherein the acid solution includes hydrochloric acid, and wherein a temperature (T) and a molarity (M) of the hydrochloric acid is within a triangular space defined by (T,M) points of (21 °C, 2.4 M), (52 °C, 2.4 M), and (52 °C, 1.2 M).

30. (Previously presented) The electrical structure of claim 26, further comprising a fluoropolymer dielectric volume bonded to said chromium volume.

31. (Previously presented) An electrical structure, comprising:

a chromium volume;

an iron-comprising body in electrical contact with the chromium volume;

an acid solution in contact with both the chromium volume and the iron-comprising body, wherein the acid solution is adapted to etch metallic chromium at a first etch rate in an absence of any present or prior contact between the metallic chromium and a body that includes iron.

32. (Previously presented) The electrical structure of claim 31, wherein the electrical structure further comprises a chromium oxide layer on the chromium volume.

33. (Previously presented) The electrical structure of claim 31, further comprising a layer of conductive metal, wherein the chromium volume includes a layer of chromium, and wherein the layer of chromium is on the layer of conductive metal.

34. (Previously presented) The electrical structure of claim 33, wherein the acid solution is not in contact with the layer of conductive metal.

35. (Previously presented) The electrical structure of claim 34, wherein the layer of conductive metal includes a metal selected from the group consisting of copper, aluminum, nickel, silver, and gold.

36. (Previously presented) The electrical structure of claim 31, wherein the chromium volume

includes the metallic chromium, wherein the acid solution includes hydrochloric acid, wherein a temperature (T) and a molarity (M) of the hydrochloric acid is within a triangular space defined by (T,M) points of (21 °C, 2.4 M), (52 °C, 2.4 M), and (52 °C, 1.2 M).

37. (Previously presented) The electrical structure of claim 31, further comprising a fluoropolymer dielectric volume bonded to said chromium volume.

38. (Previously presented) The electrical structure of claim 31, wherein the acid solution is adapted to etch the chromium volume at a second etch rate that exceeds the first etch rate.

39. (Previously presented) The electrical structure of claim 26, wherein the acid solution is adapted to etch metallic chromium at a first etch rate in an absence of any present or prior contact between the metallic chromium and a body that includes iron.

40. (Previously presented) The electrical structure of claim 39, wherein the acid solution is adapted to etch the chromium volume at a second etch rate that exceeds the first etch rate.

41. (Previously presented) An electrical structure, comprising:

a chromium volume;

an iron-comprising body in electrical contact with the chromium volume;

an acid solution in contact with both the chromium volume and the iron-comprising body; and

a layer of conductive metal, wherein the chromium volume includes a layer of chromium, and wherein the layer of chromium is on the layer of conductive metal and in direct mechanical contact with the layer of conductive metal.

42. (Previously presented) The electrical structure of claim 41, wherein the acid solution is not in contact with the layer of conductive metal.